

IN THE ABSTRACT:

Please amend the Abstract originally appearing on page 18 of the application as follows:

ABSTRACT OF THE DISCLOSURE

~~Methods and apparatus~~ Design methods and a computer-readable medium having
computer-executable instructions thereon for sidelobe suppression in a ~~radiation patterning~~
radiation-patterning tool or mask. Sidelobe artifacts are mitigated by identifying elements as a
function of the radiation wavelength for forming desired profiles on a semiconductor wafer.
Diffraction rings are calculated ~~about~~ around each of the elements to identify sidelobe
interference zones and intersections of diffraction rings are located. Sidelobe inhibitors are
located at the ~~identified locations~~ intersections of diffraction rings. A method for forming a
mask with the addition of sidelobe inhibitors as well ~~as method~~ as a method for determining the
location of placement of sidelobe inhibitors is also disclosed.